

Docket No. 197802US2S

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Wakako MORIYAMA, et al.

FILING DATE: Herewith

FOR: METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES USING THERMAL NITRIDE FILMS
AS GATE INSULATING FILMS

LIST OF INVENTORS' NAMES AND ADDRESSES

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Listed below are the names and addresses of the inventors for the above-identified patent application.

Wakako MORIYAMA	Yokohama-shi, Japan
Naoki KAI	Chigasaki-shi, Japan
Hiroaki HAZAMA	Hachioji-shi, Japan
Keiki NAGAI	Tokyo, Japan
Yuji FUKAZAWA	Yokohama-shi, Japan
Kazuo SAKI	Yokohama-shi, Japan
Yoshio OZAWA	Yokohama-shi, Japan
Yasumasa SUIZU	Tokyo, Japan

A declaration containing all the necessary information will be submitted at a later date.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.



Marvin J. Spivak
Registration No. 24,913

C. Irvin McClelland
Registration Number 21,124

09670520 09670520



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Tel. (703) 413-3000
Fax. (703) 413-2220
(OSMMN 11/98)